

## Reference number list

	1	substrate
	2	well area
5	3	buried layer
	4	epitaxial layer
	5	isolation area
	6	connection well
	7	oxide layer
10	8	nitride layer
	9	conductive electrode layer
	10	photoresist mask
	11	terminal layer
	12	well
15	13	conductive layer
	14	gate dielectric layer
	15	first gate electrode layer
	16	base area
	17	collector area
20	18	well
	19	conductive layer
	20	highly conductive layer
	20a	diffusion layer
	21a	TEOS isolation layer
25	21b	nitride isolation layer
	22	second isolation layer
	23a	ARC layer
	23b	ARC layer
	24	photoresist
30	25	photoresist
	26	isolation layer
	27	NPN base area
	28	NPN collector area
	29	LDD area
35	30	first spacing layer
	31	second spacing layer
	32	HDD area
	33	terminal layer

- 33a diffusion area
- 34 protective layer
- 35 photoresist mask
- 36 silicon layer